## Notice of References Cited Application/Control No. | Applicant(s)/Patent Under Reexamination | MERRY ET AL. | Examiner | Art Unit | Page 1 of 1

## U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	Α	US-			
	В	US-			
	С	US-			
	D	US-			
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## NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
*	U	Leverd et al. (Wsi/Poly-Si gate Stack etching for advanced dRAM applications (1999 IEEE/SEMI Advanced Semiconductor manufacturing Conference and Workshop; Sept. 8-10. 1999; Boston, MA, USA).
	V	Wolf et al (Silicon Processing for the VLSI Era; Vol. 1; 1986; Lattice Press)
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\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)

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